

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property
Organization
International Bureau

(43) International Publication Date
03 July 2025 (03.07.2025)



(10) International Publication Number
WO 2025/140918 A3

(51) International Patent Classification:

G03F 7/004 (2006.01) G03F 7/027 (2006.01)
G03F 7/025 (2006.01) G03F 7/033 (2006.01)

(21) International Application Number:

PCT/EP2024/087220

(22) International Filing Date:

18 December 2024 (18.12.2024)

(25) Filing Language:

English

(26) Publication Language:

English

(30) Priority Data:

2023-223671 28 December 2023 (28.12.2023) JP

(71) Applicant: **MERCK PATENT GMBH** [DE/DE]; Frankfurter Strasse 250, 64293 Darmstadt (DE).

(72) Inventors: **LIN, HsuanYu**; c/o Merck Electronics Ltd., Arco Tower 5F, 1-8-1, Shimomeguro, Meguro-ku, Tokyo 153-8927 (JP). **LU, Lei**; c/o Merck Electronics Ltd., Arco Tower 5F, 1-8-1, Shimomeguro, Meguro-ku, Tokyo 153-8927 (JP).

(74) Agent: **MERCK PATENT ASSOCIATION**; c/o Merck Patent GmbH, 64271 Darmstadt (DE).

(81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BN, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CV, CZ, DE, DJ, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IQ, IR, IS, IT, JM, JO, JP, KE, KG, KH, KN, KP, KR, KW, KZ, LA, LC, LK, LR, LS, LU, LY, MA, MD, MG, MK, MN, MU, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PA, PE, PG, PH, PL, PT, QA, RO, RS, RU, RW, SA, SC, SD, SE, SG, SK, SL, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, WS, ZA, ZM, ZW.

(84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, CV, GH, GM, KE, LR, LS, MW, MZ, NA, RW, SC, SD, SL, ST, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, RU, TJ, TM), European (AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, ME, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, KM, ML, MR, NE, SN, TD, TG).

Published:

- with international search report (Art. 21(3))
- before the expiration of the time limit for amending the claims and to be republished in the event of receipt of amendments (Rule 48.2(h))
- in black and white; the international application as filed contained color or greyscale and is available for download from PATENTSCOPE

(88) Date of publication of the international search report:

07 August 2025 (07.08.2025)

(54) Title: RESIST COMPOSITION AND METHOD FOR PRODUCING RESIST FILM USING THE SAME

(57) Abstract: [Problem] Provided is a resist composition having low viscosity and capable of forming a resist film that is large in thickness, and capable of sufficiently forming a pattern without bubbles generated in the resist film: [Solution] A resist composition comprising a polymer, a specific solvent, and a specific compound.



WO 2025/140918 A3